

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. #25	Serial No. 09/388,989
INFORMATION DISCLOSURE STATEMENT BY APPLICANT MAR 8 2003		Applicant Cohen, et al.	Confirmation No.: 4766
(Use several sheets if necessary)		Filing Date September 2, 1999	Group 1762
Examiner M.L. Padgett			

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1						
	A2						
	A3						
	A4						
	A5						
	A6						
	A7						
	A8						
	A9						
	A10						
	A11						
	A12						

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Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
<i>MLP</i>	B1	00/34997	06/15/2000	WO <i>Cohen et al</i>	H01L	21/311	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MLP</i>	B2	1 077 476	02/21/2001	EP	H01L	21/311	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MLP</i>	B3	56155526	01/12/1981	JP <i>Yamazaki</i>	H01L	21/205	<input type="checkbox"/>	<input checked="" type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
<i>MLP</i>	C1	"Low dielectric constant films prepared by plasma-enhanced chemical vapor deposition from tetramethylsilane" by A. Grill and V. Patel, Journal of Applied Physics, Vol. 85, pages 3314-3318, March 28, 2003 , <i>March 15, 1999</i>
<i>MLP</i>	C2	"The reduction of copper oxide thin films with hydrogen plasma generated by an atmospheric-pressure glow discharge" by Sawada, et al., J. Phys D; Appl. Phys 29 (1996) 2539-2544, printed in the UK. <i>no month</i>
<i>MLP</i>	C3	European Search Report
Examiner	<i>ML Padgett</i>	
Date Considered	<i>4/25/03</i>	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.